



5/6/02
11/21/02

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of : **Confirmati n N . 4175**
Hideo HADA et al. : Docket No. 2001_1787A
Serial No. 09/996,676 : Group Art Unit 1752
Filed November 30, 2001 : Examiner R. Ashton

POSITIVE-WORKING
PHOTORESIST COMPOSITION

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TC 1700

RESPONSE

Assistant Commissioner for Patents,
Washington, D.C.

THE COMMISSIONER IS AUTHORIZED
TO CHARGE ANY DEFICIENCY IN THE
FEES FOR THIS PAPER TO DEPOSIT
ACCOUNT NO. 23-0975

Sir:

In response to the Official Action dated July 18, 2002, the period of response having been extended for one month by the attached petition, please amend the present application as follows:

IN THE CLAIMS:

Please cancel claims 1-11 without prejudice to the subject matter thereof.

Please add new claims 12-17 as follows:

back of spec.

12. (New) A positive-working photoresist composition which comprises, as a uniform solution in an organic solvent:

(A) 100 parts by weight of a resinous compound capable of being imparted with increased solubility in an aqueous alkaline solution by interaction with an acid;

(B) from 0.5 to 30 parts by weight of a radiation-sensitive acid generating compound capable of generating an acid by irradiation with a radiation; and

(C) an organic solvent in an amount sufficient to dissolve the components (A) and (B),

Sub B1